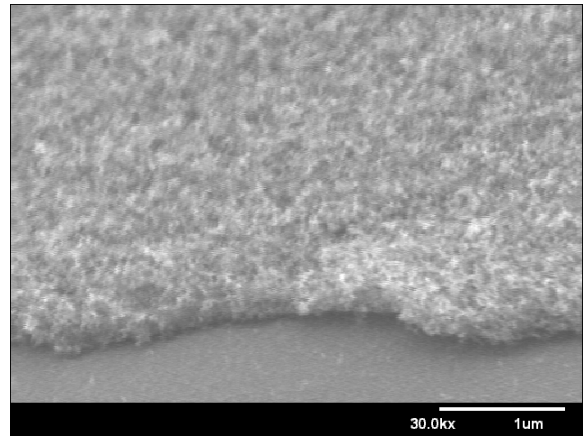
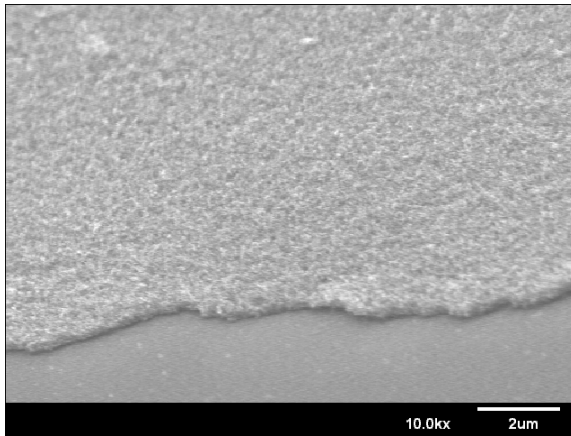
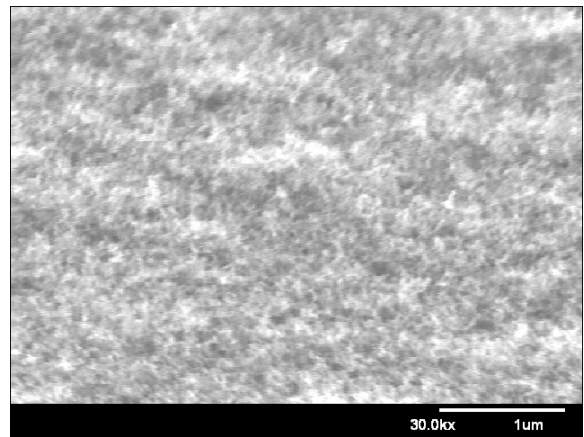
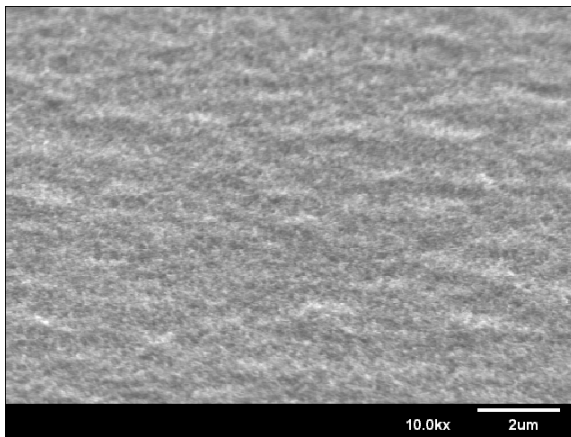


B1、550°C H₂:200 (Ni 1 nm)



B2、550°C H₂:200 (Ni 5 nm)



B3、550°C H₂:200 (Ni 7 nm)

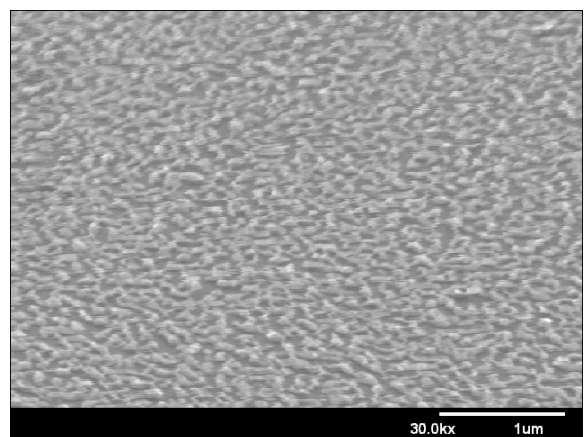
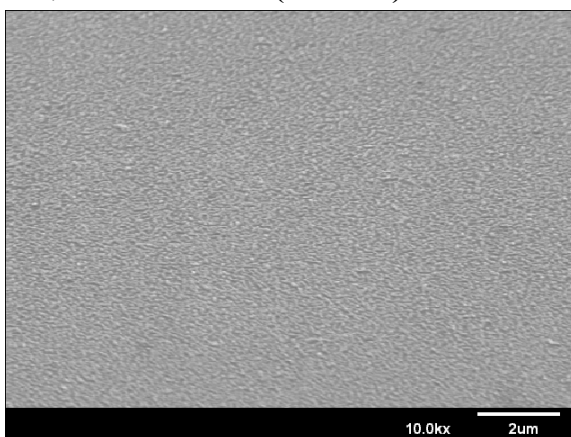
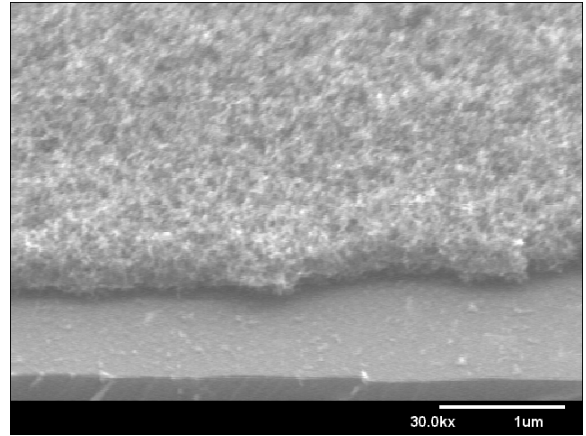
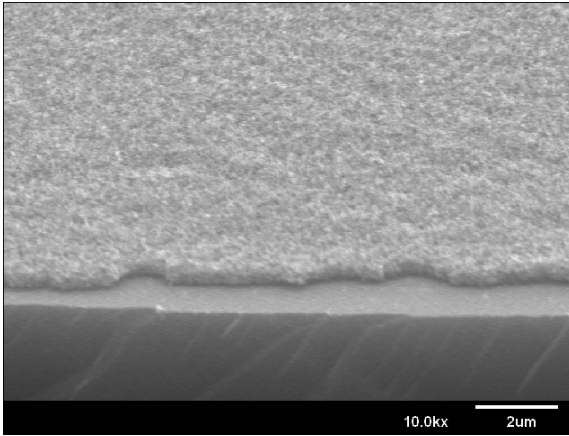
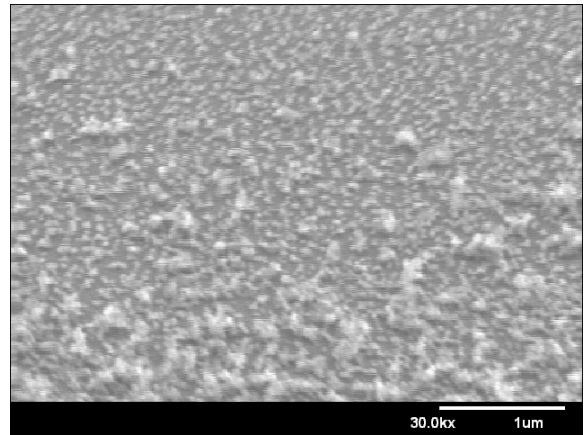
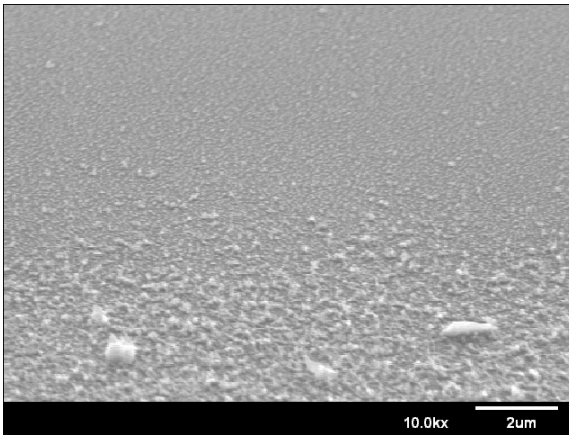


圖 4-27 製程 B 無緩衝層試件(1、2、3) 奈米碳管 SEM 圖面(10、30 kx)

C1、550°C H₂:300 (Ni 1 nm)



C2、550°C H₂:300 (Ni 5 nm)



C3、550°C H₂:300 (Ni 7 nm)

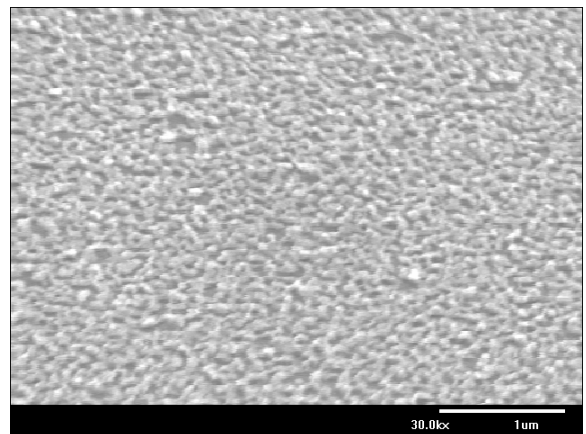
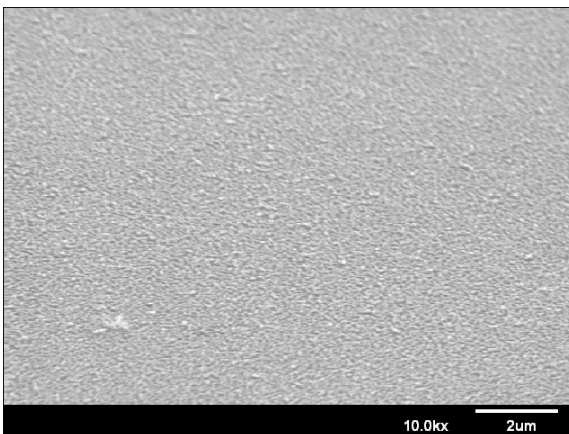


圖 4-28 製程 C 無緩衝層試件(1、2、3) 奈米碳管 SEM 圖面